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Analysis of Extended Threshold Wavelength Photoresponse in Non-symmetrical p-GaAs/AlGaAs Heterostructure Photodetectors


Abstract—We analyze the extended threshold wavelength photoresponse beyond the standard threshold limit (\( \lambda_t = 1.24 / \Delta \), where \( \Delta \) is the activation energy) in non-symmetrical p-GaAs/AlGaAs heterostructure photodetectors with a barrier energy offset. We propose that hot-cold hole carrier interactions in the p-GaAs absorber are responsible for the threshold wavelength extension. Experimental results are analyzed by considering a quasi-Fermi distribution of hot holes at a hot hole temperature \( T_{hh} \), which is much higher than the lattice temperature \( T_l \). The experimental photoresponse is fitted using an escape cone model, modified with a quasi-Fermi level \( E_{\text{quasi}} \). The simulated results are found to be in good agreement with experimental data, justifying the model used.

Index Terms—quasi-Fermi distribution, threshold wavelength, photoresponse, heterostructures, temperature.

I. INTRODUCTION

Hot-carrier effects in semiconductor heterostructures have played a major role in the development of photodetectors [1-3]. They are governed principally by carrier-carrier and carrier-phonon scattering processes, which are also of fundamental interest for the study of semiconductor physics [4-6]. The dynamics of hot carriers in bulk GaAs [4-6], and in GaAs/AlGaAs quantum wells (QWs) [7-9] and heterostructures [5, 10], have been widely studied by hot carrier spectroscopy. In general, hot carriers are created in energy states above the band edge, interact with the lattice vibrations and cold carriers through carrier-carrier interactions; this leads to a quasi-equilibrium distribution at a carrier temperature that is much higher than the lattice temperature [4, 5]. The relaxation processes of hot carriers in bulk GaAs, GaAs/AlGaAs QWs structure, and heterostructures have been studied extensively by optical spectroscopy with ultrashort laser pulses [9, 11]. In most experiments on femtosecond [9, 12] and picosecond [13] time scales, a hot electron-hole plasma is created by interband excitation and the relaxation behavior of carriers is then monitored through the time evolution of the absorption or luminescence. Such time-resolved optical experiments, using pico- and femtosecond laser pulses, allow the creation of well-defined non-equilibrium conditions, and provide direct information on the microscopic scattering processes by which the carriers relax into quasi-equilibrium [7, 9, 13].

Recently, a new concept of very long-wavelength infrared (VLWIR) photodetection was proposed by Lao et al. [14] based on hot hole effects, which enable a spectral extension of the photoresponse beyond the standard limit set by the ‘spectral rule’ \( \lambda_t = 1.24 / \Delta \), where \( \Delta \) is the activation energy. Typically, \( \lambda_t \) and \( \Delta \) is a good measure of performance in a variety of detectors, including GaAs/AlGaAs QWs [7-9] and heterostructures [5, 10]. However, there was no clear agreement between the observed extended wavelength photoresponse and the designed \( \lambda_t \) in non-symmetrical p-GaAs/AlGaAs heterostructures [14-16]. Therefore, a precise analysis is needed to understand fully the wavelength extended photoresponse; further optimize the performance; and, control the threshold of the extended wavelength photoresponse. This mechanism could then also be used to design IR photodetectors in other materials system and optimize detectors for specified threshold wavelengths.

Although various models have been reported to explain the spectral photoresponse of a variety of heterojunction detectors [17-20], none of those are able to explain the origin of the extended threshold wavelength photoresponse in non-symmetrical GaAs/AlGaAs heterojunction photodetectors. Nevertheless, it was believed that the dynamics of the hot-cold hole interaction played a crucial role [14]. In this paper, we present a theoretical explanation of the experimentally observed extended threshold wavelength photoresponse, by modelling the quasi-Fermi distribution of hot holes in the absorber. This follows the interpretation of hot carrier
spectroscopy in GaAs/AlGaAs heterostructures by Shah [5, 6] which describes the formation of hot carrier distribution under high intensity photoexcitation. The work reported by Ulbrich [21] also outlines the basic mechanisms resulting from photoexcitation of electron-hole pairs in semiconductors, but under conditions of low excitation intensity and low temperature.

II. ANALYSIS OF EXTENDED THRESHOLD WAVELENGTH PHOTORESPONSE

Schematic valence band (VB) diagrams of non-symmetrical and symmetrical p-type GaAs/AlxGa1-xAs heterostructures are illustrated in figs. 1(a)-(d), and are used to explain the possible mechanism for an extended threshold wavelength photoreponse. The structures consist of three p-type GaAs regions (doped at p = 1 × 10^{19} \text{ cm}^{-2}, based on our previous work Ref. [17], Matsik et al. (2009)): the injector, absorber and collector. By varying the Al fractions in the undoped AlxGa1-xAs barriers, an energy offset between the barriers above and below the absorber can be created (figs 1(a)-(c)), in contrast to the situation for symmetrical heterostructures (fig 1(d)). In our analysis, we assume that the non-symmetrical and symmetrical heterostructures are both excited by a broad black body source with peak intensity 2.8 mW/cm² to measure the photoreponse spectra (Perkin-Elmer system 2000 Fourier transform infrared (FTIR) spectrometer), the optical power spectrum of which was reported in [14].

In fig.1(a), \Delta_{\text{max}} is the maximum barrier height (BH) at the injector-absorber junction, \delta E_c is the barrier energy offset, \Delta_c is the BH at the absorber/collector junction, and \delta E_F is the Fermi level at the lattice temperature (T_L). In fig. 1(b), the blue wavy arrow represents an incident photon with an energy exceeding injector barrier, whilst the red wavy arrow in the absorber shows an incident photon with an energy below \Delta_{\text{max}} and represents the long wavelength absorption. The dotted blue arrow inside the absorber shows the movement of hot holes, the solid (red) dots, and an empty (green) dot represent hot holes and cold holes in the absorber, and \delta E_{\text{quas}} represents the quasi-Fermi level at hot hole temperature (T_H).

Upon incidence of light from an external optical source, hot holes are created in the injector, absorber and collector regions for both symmetrical and non-symmetrical heterostructures. However, only hot carriers arising from the injector are considered in non-symmetrical heterostructures since the collector contribution is negligible owing to energy relaxation in the thick collector barrier. Hot holes with energy > \Delta_{\text{max}} will surmount the injector barrier, and interact with cold holes in the absorber. In non-symmetrical heterostructure, a net flow of hot holes will then observed into the collector, owing to the difference in barrier heights, \delta E_c. The dynamics of hot-cold holes in the p-GaAs absorber can be explained based on hot carrier effects [5]. Upon interaction, exchange of energy takes place through hole-hole and hole-phonon scattering that leads to the formation of a quasi-Fermi distribution (E_{\text{quasi}}) in the absorber at a hot hole temperature (T_H) which is significantly greater than the lattice temperature (T_L). In figs.1(b) and (c), the solid dual arrow connecting hot holes and cold holes represent interaction and exchange of energy. The distribution of hot holes at this quasi-Fermi level will lead to escape of hot holes across the collector barrier when a long wavelength photon is absorbed (red wavy arrow) the ‘so-called’ extended threshold wavelength photoreponse; the absorbed photon would have insufficient energy to cause excitation over the injector barrier by itself.

The schematic VB diagram of the non-symmetrical heterostucture under application of negative bias is shown in fig.1(c). Upon application of a negative bias, the energy of holes passing over the injector barrier increases, leading to a greater transfer of energy to the cold holes in the absorber and this increases the number of hot holes in the absorer. Hence the number of hot holes escaping from the quasi-Fermi distribution over the collector barrier also increases, thereby increasing the strength of the extended photoreponse.

The schematic VB diagram of a symmetric heterostructure is shown in Fig. 1(d) at zero bias. Upon application of incident light from the same optical source, hot holes will surmount the
injector barrier, with contributions also arising from the absorber and collector. Furthermore, hot holes will interact with cold holes and exchange their energy, and a quasi-Fermi distribution will be formed in the absorber. However, current will flow equally across the injector and absorber barriers, from the quasi-Fermi level, and there will be no net flow of hot holes observed. Therefore, upon application of bias, photocurrent with conventional threshold wavelength will be observed in symmetric heterostructure.

The possible escape pathways of hot holes are from the heavy-hole (HH), light-hole (LH) and split-off (SO) bands to the quasi-Fermi level across the collector barrier. In the first mechanism, light absorption, from a long wavelength photon, leads to the transition of hot holes from the HH and LH band to the SO bands which is followed by internal photoemission, and escape over the collector barrier [17]. In the second mechanism, a portion of the hot holes lose some of their energy via different scattering mechanism and relax to the band edge of the LH or HH bands and then escape over the collector barrier [17]. The escape probability can be determined by using an escape cone model [22].

III. THEORETICAL SIMULATION USING ESCAPE CONE MODEL

To validate that the quasi-Fermi distribution (E_{\text{quasi}}) of hot holes in the p-GaAs absorber is responsible for the extended wavelength photoresponse, we have used an escape-cone model [22] to simulate the extended photoresponse spectrum. In this model, free-carrier absorption, described by Drude theory, is considered as the primary optical absorbing mechanism [19]. The responsivity of the heterostructure detector depends on the total quantum efficiency (\eta) and is given by the following relation [17-19]

\[ R = \frac{q \eta \lambda}{hc} \]  

where \( q \) is the electron charge, \( c \) is the speed of light and \( h \) is the Planck’s constant. The total quantum efficiency (\eta) is the product of the photon absorption probability (\eta_a), the internal quantum efficiency (\eta_i), and the hot carrier transport probability (\eta_h), and is given by:

\[ \eta = \eta_a \eta_i \eta_h \]  

The value of \( \eta_a \) and \( \eta_i \) were calculated using the model described in [18, 19]. \( \eta_a \) was calculated using an escape cone model [22], and is defined as the ratio of the number of carriers at the excited \( E_{\text{quasi}} \) that have sufficient kinetic energy to overcome the barrier, associated with the momentum component normal to the interface, to the total number of excited carriers. Calculation of \( \eta_i \) can take into account scattering with cold holes and phonons, as given by [22]:

\[ \eta_i = \eta_0 \left[ 1 - \frac{\eta_0}{\eta_M} \right] \eta_1 + \left[ 1 - \frac{\eta_0}{\eta_M} \right] \left[ 1 - \frac{\eta_1}{\eta_\text{M}} \right] \left[ 1 - \frac{\eta_1}{\eta_\text{M}} \right] ... \]  

where \( \eta_n = \eta_0 (E - n h \nu) \) and \( \gamma = I_h / (I_e + I_h) \)

Here, \( n \) is the number of scattering events, \( \eta_M \) is the maximum quantum efficiency, and the value of \( \eta_0 \) is defined as the fraction of hot holes captured prior to any bulk scattering events, and is given by,

\[ \eta_0 = \frac{L_s^2}{W} \left( 1 - e^{-W/L_s} \right)^{1/2} \eta_{\text{ideal}} \]  

where \( W \) is the width of absorber, and \( \eta_{\text{ideal}} \) is the ideal quantum efficiency. \( L_s = I_h \times L_p / (I_e + I_h) \) is the reduced scattering length for hole-cold holes, \( L_p \) is the hole-hole scattering length for hot-cold holes and \( L_e \) represents elastic scattering of hot holes with phonons and impurities, and multiple reflections of the excited hot holes from the surfaces of the absorber [22]. In this simulation, we have only modified the escape cone model by changing the Fermi distribution at \( E_F \) to the perturbed \( E_{\text{quasi}} \).

IV. COMPARISON WITH EXPERIMENTS

The simulated photoresponse obtained from the escape-cone model with a modified hot-hole Fermi distribution, leading to a modified effective \( \Delta \), were compared with experimentally measured results. The spectral photoresponse of three heterostructure photodetectors with symmetrical (LH1002) and non-symmetrical (SP1001, SP1007) configurations were measured at 5.3 K; fabrication and characterization have already been reported elsewhere [14, 23, 24]. The valence band (VB) diagram of sample LH1002 with a p-type doped GaAs absorber sandwiched between two flat (60 nm) Al_{1-x}Ga_xAs barriers is shown in fig 2(a). Fig. 2(b) and 2(c) show VB diagrams of SP1001 (flat injector barrier with \( \Delta E_v = 0.10 \text{ eV} \)) and SP1007 (graded injector barrier with Al fraction varying from 0.45 to 0.75 and \( \Delta E_v = 0.10 \text{ eV} \)), respectively. The activation energy (\( \Delta \)) is defined as the energy difference between the Fermi level in the p-type GaAs and the valence band-edge of the Al_{1-x}Ga_xAs barrier. For Al mole fraction values (\( x \)) of 0.45, 0.57 and 0.75, \( \Delta \) is calculated to be 0.25 eV, 0.32 eV and 0.42 eV, respectively. Details of \( \Delta \) and \( \Delta E_v \) for all the samples, calculated by taking into account band offsets at the heterointerface and doping-induced bandgap narrowing [14], are compared in Table 1.

Spectral responses were measured using a Perkin–Elmer system 2000 Fourier transform infrared (FTIR) spectrometer. A bolometer with known sensitivity was used for background measurements and calibrating the responsivity. In general, holes in the p-GaAs absorber interact with incident photons and, when they gain sufficient energy to surmount the barrier, travel in both directions, i.e. towards the bottom (BC) and top (TC) contacts, giving rise to forward and reverse photocurrents. As a consequence, the net photocurrents are determined by the balance of the photoemission efficiencies associated with movement of holes in the forward and reverse directions [23].

<table>
<thead>
<tr>
<th>Samples</th>
<th>Activation Energy (eV)</th>
<th>Barrier Energy offset ( \Delta E_v ) (eV)</th>
</tr>
</thead>
<tbody>
<tr>
<td>LH1002</td>
<td>0.32</td>
<td>0.32</td>
</tr>
<tr>
<td>SP1001</td>
<td>0.42</td>
<td>0.32</td>
</tr>
<tr>
<td>SP1007</td>
<td>0.42</td>
<td>0.25</td>
</tr>
</tbody>
</table>

TABLE 1: COMPARISON OF THE VALUES OF ACTIVATION ENERGY AND ENERGY OFFSET FOR LISTED DEVICES. IN ALL SAMPLES THE GaAS ABSORBER HAS A DOPING DENSITY OF \( p = 1 \times 10^{19} \text{ cm}^{-3} \).
Under zero applied bias, in LH1002 ($\delta E_v = 0$) the net flow of photoexcited holes in both directions is the same. However, for SP1001 and SP1007, because $\delta E_v = 0.10$ eV, the net photoemission efficiency is not equal owing to the difference between the heights of the barriers below and above the absorber. Therefore, there exists a net flow of current from absorber to the collector, even at zero bias. The spectral photoresponse of LH1002 at 5.3 K for different biases, ranging from 0 to -0.5 V is shown in fig. 2(d). The threshold energy of spectral photoresponse is determined by temperature-dependent internal photoemission spectroscopy (TDIPS) fitting, where the quantum yield defined as the number of collected hot holes per incident photon is proportional to the multiplication of the spectral responsivity with photon energy[25]. The quantum yield is plotted as a function of photon energy in the inset of fig. 2(d), and used to calculate the threshold energy of the photoresponse. The details of the TDIPS principle and the formalism for interpreting yield spectra by a fitting procedure are described in Ref.[25]. The threshold energies calculated from TDIPS fitting are consistent with the designed wavelength photoresponse when the bias is between 0 to -0.5 V [24]. The small increase in the TDIPS threshold wavelength with bias is a result of the image force lowering effect [24] present in heterostructures.

Fig. 3 (a) shows the spectral response of sample SP1001 at 5.3 K for the voltages ranging from 0 V to -0.5 V. An extended threshold wavelength response up to ~36 μm is observed between -0.3 V and -0.5 V, together with the conventional response. Further, increasing bias voltage >0.6 V, intensity of extended photoresponse started decreasing and at higher than >-1.2 V, extended threshold photoresponse became zero and photoresponse with conventional threshold wavelength is observed. The inset of fig. 3(a) shows the weak extended photoresponse of SP1001 at zero bias. We can interpret this as, due to barrier energy offset in the heterostructure, an extended photoresponse is seen at 0 V in SP1001, whereas no extension was observed in the symmetric barrier structure as shown in fig. 2(d).

![Diagram](image)

**Fig. 2** (a) The VB diagram of sample LH1002, which has a symmetric band configuration ($\delta E_v = 0$) and consists of two AlGaAs flat barriers with equal thickness and equal mole fraction, i.e. $x_1 = x_2 = x_3 = 0.57$. (b) Non-symmetrical VB structure of sample SP1001, where $x_1 = 0.75$, $x_2 = 0.75$ and $x_3 = 0.57$, and $\delta E_v = 0.10$ eV is the energy offset between the barriers below and above the absorber. $\Delta_{\text{opt}} = 0.42$ eV and $\Delta_{\text{c}} = 0.32$ eV (c) Non-symmetrical graded barrier structure of sample SP1007 which has a similar device structure to SP1001 except that $x_1 = 0.75$, $x_2 = 0.45$ and $x_3 = 0.57$. $\delta E_v = 0.10$ eV, with $\Delta_{\text{opt}} = 0.42$ eV and $\Delta_{\text{c}} = 0.25$ eV (d) Spectral response of LH1002 at 5.3 K, for different bias voltages, ranging from 0 to -0.5 V. The inset shows TDIPS fitting of the experimental data to determine the threshold energy; the observed spectral response matches the designed threshold wavelength.

![Graph](image)

**Fig. 3** (a) Experimental photoresponse of SP1001 ($\delta E_v = 0.10$ eV) at voltages range from -0.3 to -0.5 V, an extended response up to ~36 μm is observed. However, due to a relatively high noise level, the exact threshold wavelength is not clear. Inset: extended photoresponse at 0 V, clearly showing a weak extended photoresponse starting at 0 V for SP1001 (b) Experimental photoresponse of SP1007 at a bias voltage range from -0.05 V to -0.1 V, upon application of bias extended threshold wavelength almost remains constant, however, responsivity increases with bias. Marked features are associated with GaAs and AlAs-like phonons. Inset: TDIPS fitting to determine the accurate threshold energy ($\Delta$) of the experimental photoresponse of SP1007 at -0.06 V; the determined value of $\Delta$ is 0.0214 eV.
Fig. 3(b) shows spectral photoresponse of SP1007 at different bias voltage range. By TDIPS fitting (as shown in Inset of Fig. 3(b)), an extended threshold wavelength up to ~58 μm (-0.06 eV) is detected. It is observed from fig. 3(a) and (b), upon application of bias, responsivity increases whereas extended threshold wavelength remains fairly constant for the spectral response of SP1001 and SP1007 at 5.3 K.

As can be seen from the schematic diagrams in figs. 2 (b) and (c), SP1001 and SP1007 have similar device structures except the graded injector barrier in SP1007. Due to the graded barrier at the injector, the number of hot holes moving from the injector to the absorber is higher in SP1007. Thus, a longer extended threshold wavelength is observed in SP1007 due to the features seen around 40-50 μm as compared to SP1001. The sharp dip between 38-39 μm is due to the phonon absorption observed in GaAs substrates. In addition, a very strong response in the 10-25 μm range is observed in SP1001, however a physics explanation for these observations is not very much clear. Recently, an extended photoresponse of greater than 60 μm has been reported for a device structure similar to SP1007, except δEν = 0.19 eV [15, 16].

The GaAs substrates have multiple phonon absorption lines in the region of interest that results in the valleys observed in the responsivity spectra. The marked features observed in the responsivity spectra (fig.3 (b)) are associated with GaAs and AlAs-like phonons which is already discussed elsewhere[14]. It is noted that the experimental photoresponse also exhibits two shallow valley at 22.5 μm and 32.5 μm which corresponds well with the two phonon absorption observed in GaAs substrates[26, 27].

V. SIMULATION OF EXPERIMENTAL PHOTORESPONSE

To simulate the extended threshold wavelength experimental photoresponse using an escape-cone model with a hot-hole distribution, a precise wavelength threshold in the spectral photoresponse is needed. In SP1001 (δEν = 0.10 eV), an extended photoresponse up to ~36 μm is clearly observable (fig. 3(a)). However, the precise threshold wavelength is not clear. For SP1007, a much clearer wavelength threshold is detected, and hence we discuss simulations only of the experimental photoresponse of SP1007 in this section. A threshold energy of Δ = 0.0214 eV at -0.06 eV, as determined by TDIPS fitting (in Inset of fig. 3(b)), is used as one of the fitting parameters in the simulation, determining the long-wavelength end of the theoretical photoresponse. By using the Δ from TDIPS fitting and value of valence band edge [25], the E_{quasi} (i.e. valence band edge - Δ) close to 0.30 eV is determined. This is an empirical value which is used to calculate the escape probability of hot holes across the quasi-Fermi level, for the hole density in the absorber is equal to or less than that of the doping level in the absorber.

To simulate spectral photoresponse, the total quantum efficiency is calculated by escape-cone model[22]. For a given value of E_{quasi}, L_{th} and L_{p} values are optimized to get significant fitting to experimental photoresponse. Fig. 4 compare experimental photoresponse (black solid line) of SP1007 (-0.06 V) to the escape cone model simulated photoresponse (blue dashed line). As simulated photoresponse is clearly matched with experimental photoresponse. This simulated photoresponse when corrected for the multi phonon absorptions corresponds to 22.5 μm and 32.5 μm by using Gaussian absorption features, should further improve the fitting to be an exact match as shown previously [26]. The L_{th} ~ 300 nm and L_{p} ~ 480 nm are scattering length value, where the value of L_{p} > L_{th} indicates hole-phonon scattering is dominant at the quasi-Fermi distribution. Based on literature [9, 12], an average relaxation time of the order femtoseconds is estimated. The simulated results can be interpreted based on hot-cold hole dynamics in p-GaAs absorber that when hot holes interact with cold holes and finally reached quasi-Fermi distribution close to ~ 0.30 eV, the escape of hot holes from that E_{quasi} by absorption of long wavelength photon gives extended threshold photoresponse.

VI. CONCLUSION

We have proposed a mechanism to explain the extended threshold wavelength photoresponse in non-symmetrical p-GaAs/AlGaAs heterostructure photodetectors based on hot carrier effects. Based on the mechanism, we have simulated the extended threshold wavelength photoresponse of a non-symmetrical graded barrier heterostructures (SP1007) using a quasi-Fermi distribution of hot holes with T_{H} >> T_{L} = 5.3 K. The as simulated photoresponse agreed well with the experimental photoresponse for E_{quasi} ~ 0.30 eV, L_{th} ~ 300 nm and L_{p} ~ 480 nm which also justifying the model used.

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